

	Hits	Search Text	DBs
1	13	((illumination or light or radiation) same source) and ((expos\$4 or project\$4 or lithograph\$6) same (system or apparatus or device)) and ((optical or project\$4) same lens\$4) and ((mask or reticle or photomask) same (mount or stage or hold\$4)) and (substrate or workpiece) and ((mask or reticle or photomask) same slit\$4 same (opaque or light\$6block\$4 or light\$4shield\$5 or non\$4transmis\$5 or non\$4transparen\$3) same ((first or second) near9 (surface or side)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
2	2	((illumination or light or radiation) same source) and ((expos\$4 or project\$4 or lithograph\$6) same (system or apparatus or device)) and ((optical or project\$4) same lens\$4) and ((mask or reticle or photomask) same (mount or stage or hold\$4)) and (substrate or workpiece) and ((mask or reticle or photomask) same slit\$4 same (opaque or light\$6block\$4 or light\$4shield\$5 or non\$4transmis\$5 or non\$4transparen\$3)) and ((mask ro reticle or photomask) same ((first or second) near9 (surface or side))) and ((interference near12 pattern) same (imag\$4 or record\$4 or imprint\$4) same intensit\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
3	1	((illumination or light or radiation) same source) and ((expos\$4 or project\$4 or lithograph\$6) same (system or apparatus or device)) and ((optic\$4 or project\$4) same lens\$4) and ((mask or reticle or photomask) same (mount or stage or hold\$4)) and (substrate or workpiece) and ((mask or reticle or photomask) same slit\$4 same (opaque or light\$6block\$4 or light\$4shield\$5 or non\$4transmis\$5 or non\$4transparen\$3) same (contrast or distribut\$4)) and ((interference near12 pattern) same (imag\$4 or record\$4 or imprint\$4) same intensit\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
4	1	((illumination or light or radiation) same source) and ((expos\$4 or project\$4 or lithograph\$6) same (system or apparatus or device)) and ((optic\$4 or project\$4) same lens\$4) and ((mask or reticle or photomask) same (mount or stage or hold\$4)) and (substrate or workpiece) and ((mask or reticle or photomask) same slit\$4 same (opaque or light\$6block\$4 or light\$4shield\$5 or non\$4transmis\$5 or non\$4transparen\$3) same (contrast or distribut\$4)) and ((interference near12 pattern) same contrast same intensit\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
5	2	((illumination or light or radiation) same source) and ((expos\$4 or project\$4 or lithograph\$6) same (system or apparatus or device)) and ((optic\$4 or project\$4) same lens\$4) and ((mask or reticle or photomask) same (mount or stage or hold\$4)) and (substrate or workpiece) and ((mask or reticle or photomask) same slit\$4 same (opaque or light\$6block\$4 or light\$4shield\$5 or non\$4transmis\$5 or non\$4transparen\$3) same (contrast or distribut\$4 or (numerical near9 aperture))) and ((interference near12 pattern) same intensit\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
6	3	((illumination or light or radiation) same source) and ((expos\$4 or project\$4 or lithograph\$6) same (system or apparatus or device)) and ((optic\$4 or project\$4) same lens\$4) and ((mask or reticle or photomask) same (mount or stage or hold\$4)) and (substrate or workpiece) and ((mask or reticle or photomask) same slit\$4 same (opaque or light\$6block\$4 or light\$4shield\$5 or non\$4transmis\$5 or non\$4transparen\$3)) and ((interference near12 pattern) same intensit\$4 same (contrast or distribut\$4 or (numerical near9 aperture)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
7	3	(illumination or light or radiation) and ((optic\$4 or project\$4) same lens\$4) and ((mask or reticle or photomask) same (mount or stage or hold\$4)) and (substrate or workpiece) and ((mask or reticle or photomask) same slit\$4 same (opaque or light\$6block\$4 or light\$4shield\$5 or non\$4transmis\$5 or non\$4transparen\$3)) and ((interference near12 pattern) same intensit\$4) and ((mask or reticle or pattern\$4 or photomask) same slit same (contrast or distribut\$4 or (numerical near9 aperture)) same intensit\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
8	3	(illumination or light or radiation) and ((optic\$4 or project\$4) same lens\$4) and ((mask or reticle or photomask) same (mount or stage or hold\$4)) and (substrate or workpiece) and ((mask or reticle or photomask) same slit\$4 same (opaque or light\$6block\$4 or light\$4shield\$5 or non\$4transmis\$5 or non\$4transparen\$3)) and ((interference near12 pattern) same intensit\$4) and (pattern\$4 same slit same (contrast or distribut\$4 or (numerical near9 aperture)) same intensit\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
9	4	((illumination or light or radiation) same (distribution or characteri\$7)) and ((optic\$4 or project\$4) same lens\$4) and ((mask or reticle or photomask) same (mount or stage or hold\$4)) and (substrate or workpiece) and ((mask or reticle or photomask) same slit\$4 same (opaque or light\$6block\$4 or light\$4shield\$5 or non\$4transmis\$5 or non\$4transparen\$3)) and ((interference near12 pattern) same intensit\$4) and (slit same (contrast or distance or width))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
10	2	((illumination or light or radiation) same (distribution or characteri\$7)) and ((optic\$4 or project\$4) same lens\$4) and ((mask or reticle or photomask) same slit\$4 same (opaque or light\$6block\$4 or light\$4shield\$5 or non\$4transmis\$5 or non\$4transparen\$3)) and ((interference near12 pattern) same intensit\$4) and ((record\$3 or image or imprint\$4 or pattern\$4) same (expos\$4 or irradiat\$4 or illuminat\$4) same develop\$4) and (sens\$4 or monitor\$5 or (insitu near8 monitor\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
11	6	((illumination or light or radiation) same (distribution or characteri\$7)) and ((optic\$4 or project\$4) same lens\$4) and ((mask or reticle or photomask) same slit\$4 same (opaque or light\$6block\$4 or light\$4shield\$5 or non\$4transmis\$5 or non\$4transparen\$3)) and (((interference near12 pattern) or interference) same intensit\$4) and ((record\$3 or imag\$4 or imprint\$4 or pattern\$4) same (expos\$4 or irradiat\$4 or illuminat\$4) same develop\$4) and (sens\$4 or monitor\$5 or (insitu near8 monitor\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
12	6	((illumination or light or radiation) same wavelength same (determin\$4 or calculat\$4 or apply\$4)) and ((optic\$4 or project\$4) same lens\$4) and ((mask or reticle or photomask) same (mount or stage or hold\$4)) and (substrate or workpiece or wafer or device) and ((mask or reticle or photomask) same slit\$4 same (distance or width)) and ((mask or reticle or photomask) same (opaque or \$6block\$4 or \$9shield\$5 or \$6transmis\$5 or non\$4transparen\$3)) and ((interference near12 pattern) same intensit\$4) and ((mask or reticle or pattern\$4 or photomask) same (contrast or distribut\$4 or depth or thickness) same (NA or (numerical near9 aperture)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
13	4	((illumination or light or radiation) same (wavelength or characterist\$4 or distribut\$3)) and ((optic\$4 or project\$4) same lens\$4) and (substrate or workpiece or wafer or device) and ((mask or reticle or photomask) same slit\$4 same (distance or width) same (adjust\$4 or variable or vary\$4 or determin\$4 or calculat\$4 or chang\$4)) and ((mask or reticle or photomask) same (opaque or \$6block\$4 or \$9shield\$5 or \$6transmis\$5 or \$5transparen\$3)) and ((interference near22 pattern) same intensit\$4) and ((mask or reticle or photomask) same (contrast or distribut\$4 or depth or thickness) same (NA or (numerical near9 aperture)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
14	8	((mask or reticle or photomask) same slit\$4 same (distance or width) same (adjust\$4 or variable or vary\$4 or determin\$4 or calculat\$4 or chang\$4)) and ((mask or reticle or photomask) same (opaque or \$6block\$4 or \$9shield\$5 or \$6transmis\$5 or \$5transparen\$3)) and (interference same pattern same intensit\$4) and ((mask or reticle or photomask) same (depth or thickness) same (NA or (numerical near9 aperture)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
15	5	((("5237388") or ("20020021460") or ("6239876") or ("6346981") or ("6356345"))).PN.	US-PGPUB; USPAT

	Hits	Search Text	DBs
16	3	((optic\$4 or project\$4) same lens\$4) and (substrate or workpiece or wafer or device) and ((mask or reticle or photomask) same (slit\$4 or opening or aperture) same (distance or width)) and ((mask or reticle or photomask) same (opaque or \$6block\$4 or \$9shield\$5 or \$6transmis\$5 or non\$4transparen\$3)) and ((interference near12 pattern) same intensit\$4 same contrast) and ((determin\$4 or calculat\$4 or adjust\$4) same (contrast or distribut\$4 or depth or intensit\$3) same ((fourier near3 transform\$5) or fourier or FT))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
17	6	(optic\$4 or lens\$4 or (projection near9 lens)) and (substrate or workpiece or wafer or device) and ((mask or reticle or photomask) near16 (slit\$4 or opening or aperture)) same (distance or width)) and ((mask or reticle or photomask) same (opaque or \$6block\$4 or \$9shield\$5 or \$6transmis\$5 or non\$4transparen\$3 or chromium or Cr)) and ((interference near12 pattern) same (reticle or mask or photomask)) and ((interference or diffract\$4) same intensit\$4 same contrast) and ((determin\$4 or calculat\$4 or adjust\$4) same (contrast or distribut\$4 or depth or intensit\$3) same ((fourier near3 transform\$5) or fourier or FT))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
18	4	((optic\$4 or project\$4) same lens\$4) and (substrate or workpiece or wafer or device) and ((mask or reticle or photomask) same (slit\$4 or opening or aperture)) and ((mask or reticle or photomask) same (opaque or \$6block\$4 or \$9shield\$5 or \$6transmis\$5 or non\$4transparen\$3)) and (interference near12 pattern) and ((substrate or wafer or workpiece) same (photoresist or photosensitive) same (expos\$4 or illuminat\$4 or irradiat\$4) same develop\$4) and ((imag\$4 or pattern) same (photoresist or photosensitive or (radiation near4 sensitive)) same (height or profile) same (nanoindentor or microscope or AFM or SEM or nanoscope or dektak))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
19	3	((optic\$4 or project\$4) same lens\$4) and (substrate or workpiece or wafer or device) and ((mask or reticle or photomask) same (slit\$4 or opening or aperture)) and (interference near12 pattern) and ((substrate or wafer or workpiece) same (photoresist or photosensitive) same (expos\$4 or illuminat\$4 or irradiat\$4) same develop\$4) and ((imag\$4 or pattern) same (photoresist or photosensitive or (radiation near4 sensitive))) same (height or profile) same (nanoindentor or microscope or AFM or SEM or nanoscope or dektak) same profil\$7)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
20	3	(substrate or workpiece or wafer or device) and ((mask or reticle or photomask) same (slit\$4 or opening or aperture)) and (interference near12 pattern) and ((substrate or wafer or workpiece) same (photoresist or photosensitive) same (expos\$4 or illuminat\$4 or irradiat\$4) same develop\$4) and ((imag\$4 or pattern) same (photoresist or photosensitive or (radiation near4 sensitive))) same (height or profile) same (nanoindentor or microscope or AFM or SEM or nanoscope or dektak) same profil\$7)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
21	8	(substrate or workpiece or wafer or device) and (interference near12 pattern) and ((substrate or wafer or workpiece) same (photoresist or photosensitive) same (expos\$4 or illuminat\$4 or irradiat\$4) same develop\$4) and ((imag\$4 or pattern) same (photoresist or photosensitive or (radiation near4 sensitive)) same (height or profile) same (nanoindenter or microscope or AFM or SEM or nanoscope or dektak) same profil\$7)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB